

Fabrication of graphitic-carbon suspended nanowires through mechano-electrospinning of photocrosslinkable polymers

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Motivation & Problem Statement



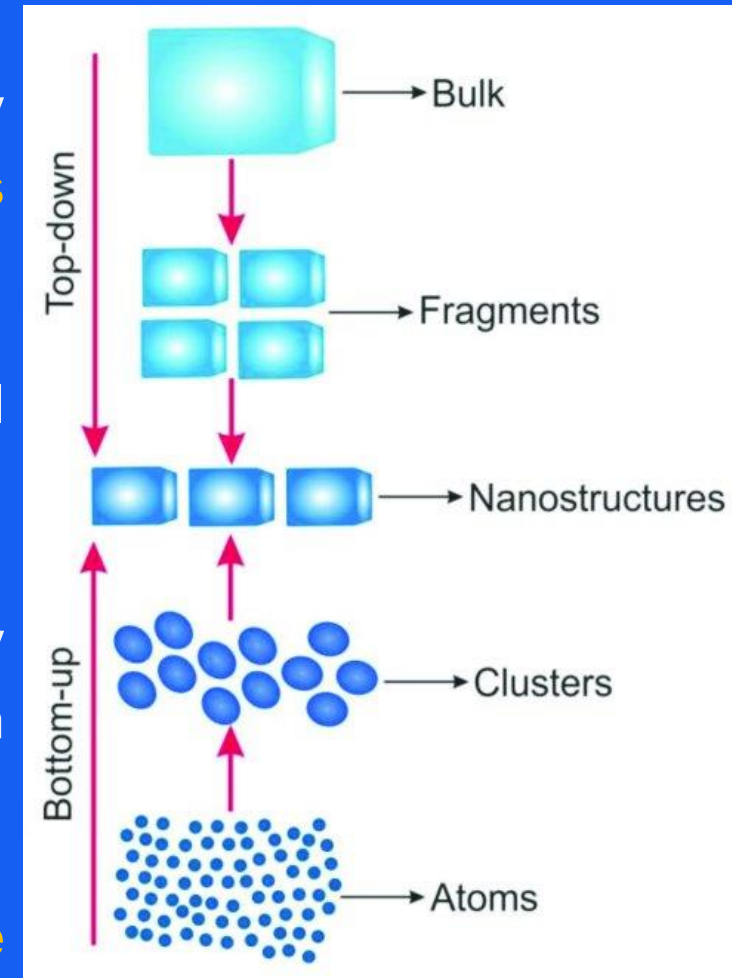
Current approaches for the fabrication of carbon nanowires (CNWs)

Lithography
Physical & Optical Limitations

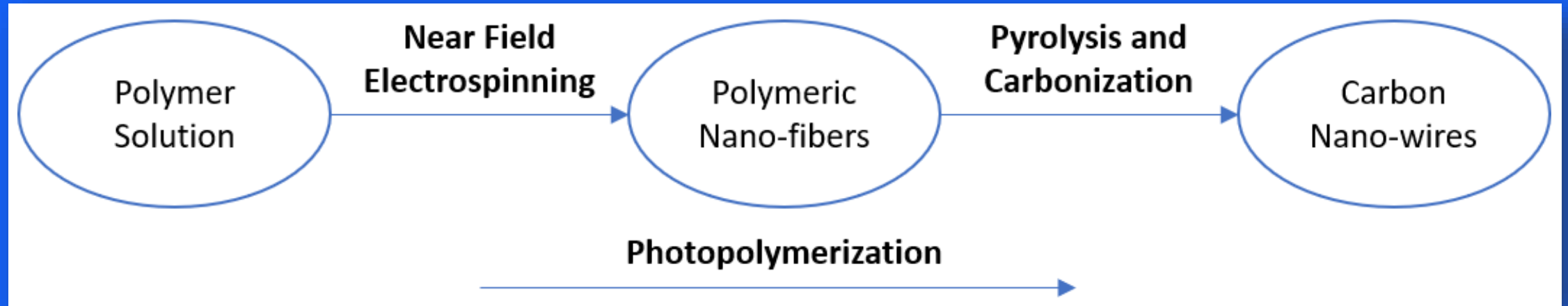
Near-Field Electrospinning (NFES)
Can fabricate Suspended Nanowires w/Spatial Control

Self-assembly
Limited Length and Random Orientation

Two-Photon Polymerization (TPP)
Slow (mm per sec) & Expensive



Thesis Overview



Design polymer solutions that can be **electrospun** by NFES, **photopolymerized**, and then **pyrolyzed** into conductive carbon nano-wires.



Polymer Solution Parameters



SU-8 Carbon Structures

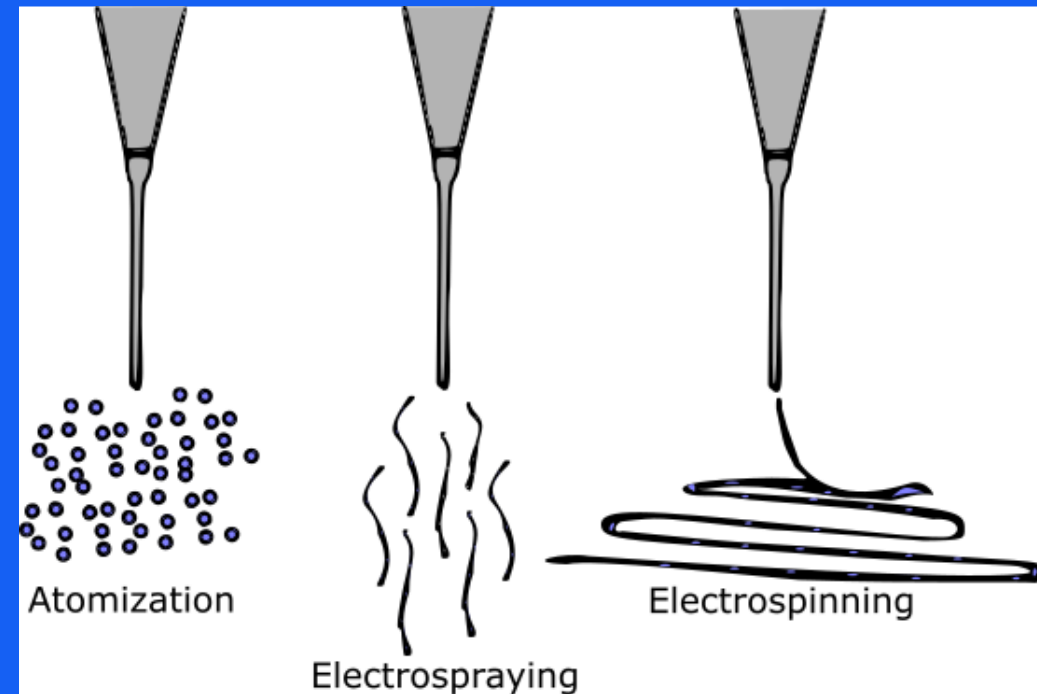
The production of C-MEMS:

1. Polymer patterning through **photolithography**
2. Carbonization through **pyrolysis**

However, **SU-8 as is can not electrospin**

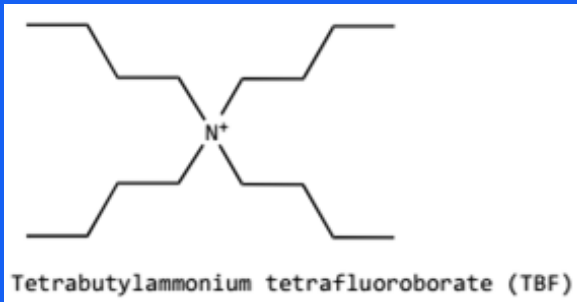
SU-8 does not have the right viscosity & solution conductivity

SU-8 is design for photolithography

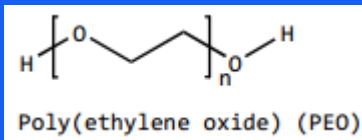


Making SU-8 spunable (by Braulio & Ricardo)

SU-8 + TBF + PEO



→ To increase the **solution conductivity**



→ To provided the required **viscosity**

... both needed for **smooth PEO flow** during electrospinning



Results with amended SU-8

The modified solution is spunable

Fiber diameter before pyrolysis of 4.966 μm

Fiber diameter after pyrolysis of 204 nm

But, somewhat pyrolyzable

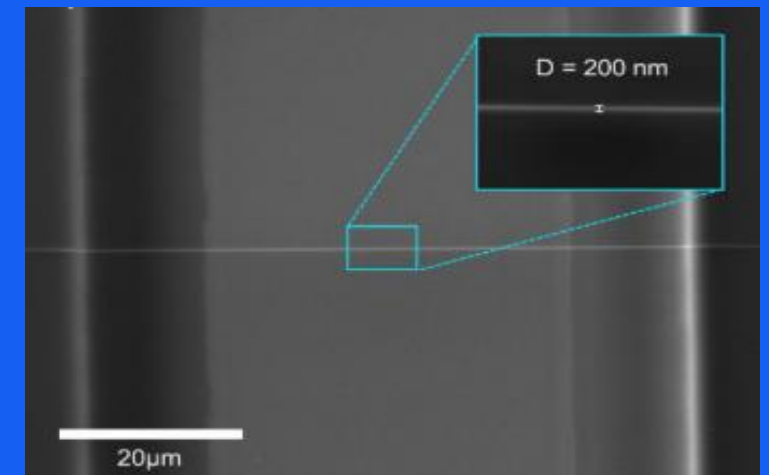
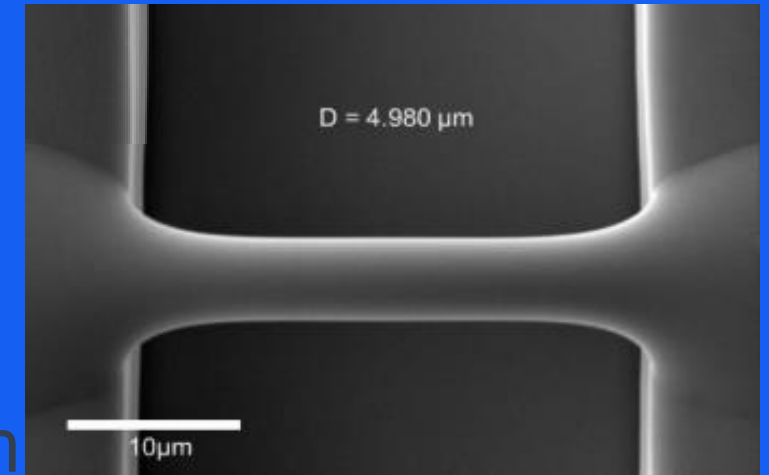
Fiber resistivity from 407 K Ω to 1.727 M Ω

Fiber yield rate of 81 %

Achieved with:

wt% PEO	SU-8 2002 [mg]	PEO [mg]	TBT [mg]
0.25	2246	5.65	11.32

= 2 ml of solution



Implications of PEO, as it introduces oxygen to the solution

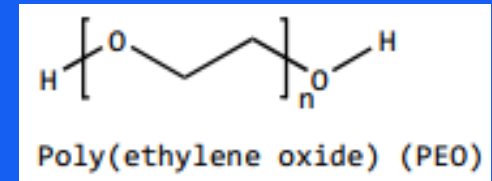
The **fiber yield rate** and **fiber conductivity** are impacted negatively.



Some samples are destroyed during pyrolysis



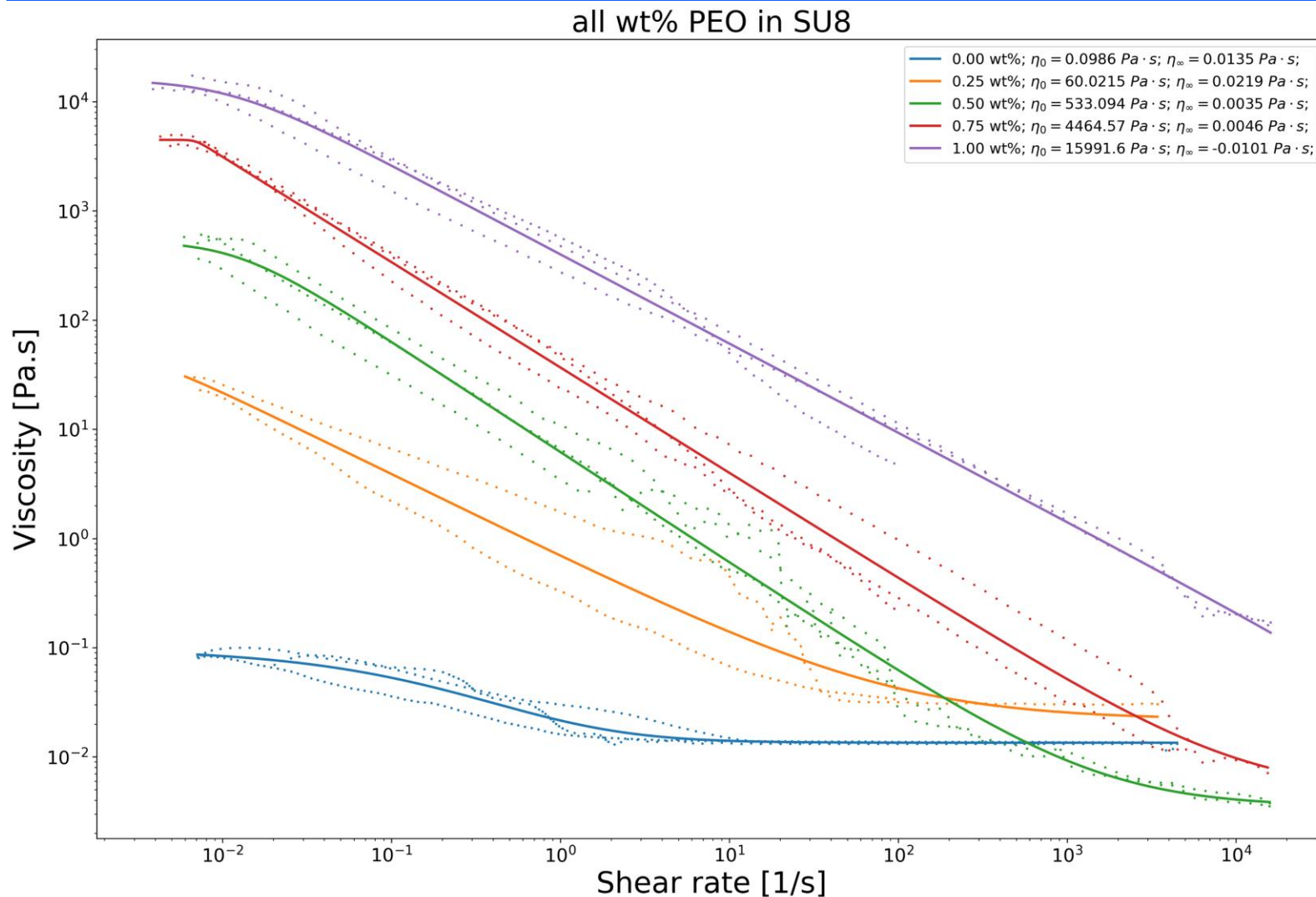
High variance in the obtained conductivity across samples.



In the presence of oxygen, the char yield decreases. This is due to the oxidation on the char.



Rheology of the amended SU-8 solution (0.25 wt%)

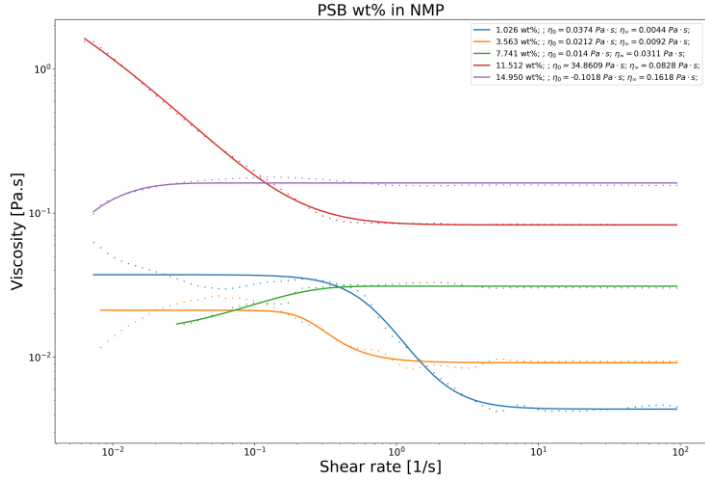


The 0.25 wt% sample (orange line) has a zero-shear viscosity (ZSV) of **60 Pa.s**

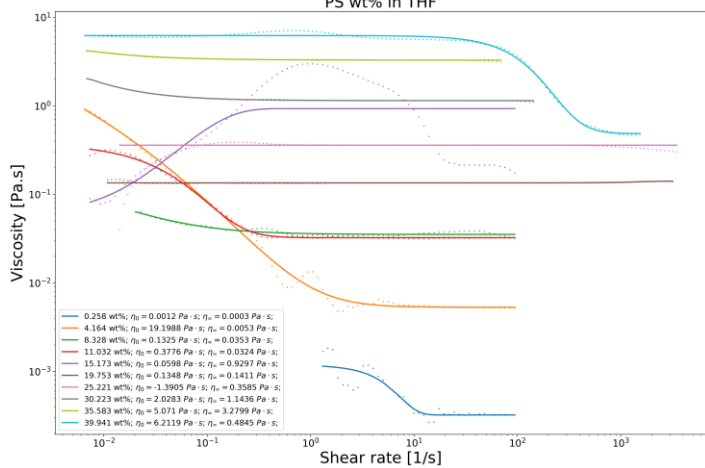
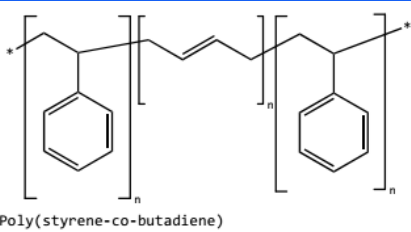


Let's discover new polymer solutions with similar rheology (and **no oxygen**)

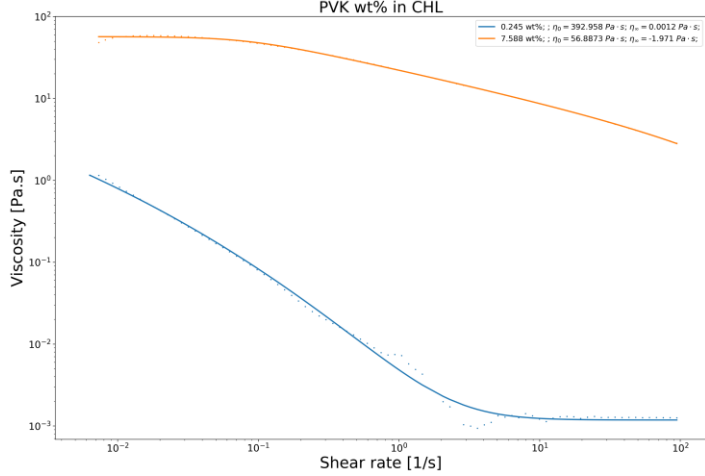
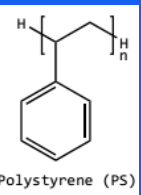




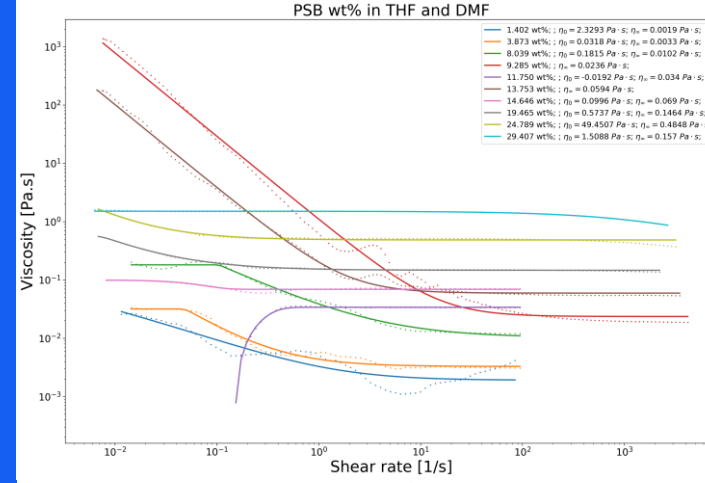
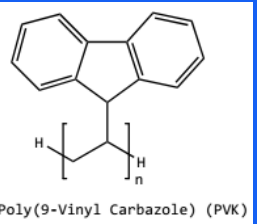
15 wt% in NMP



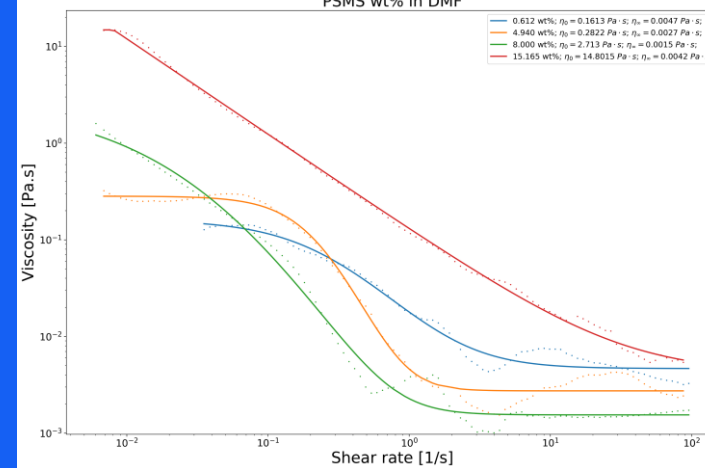
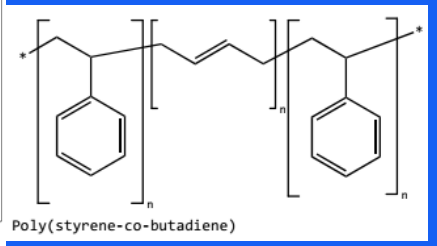
35 wt% in THF



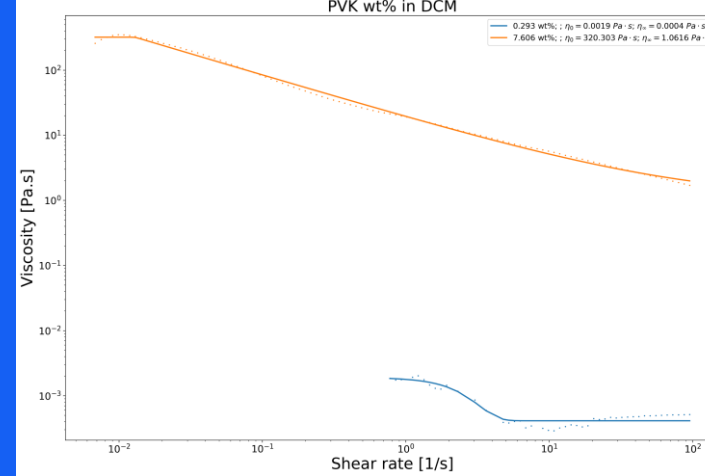
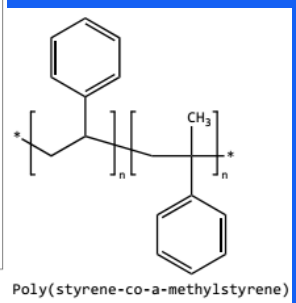
8 wt% in CHL



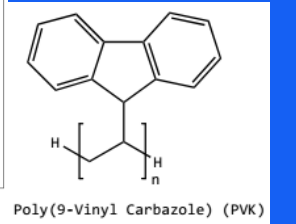
25 wt% in THF & DMF



15 wt% in DMF



7 wt% in DCM



NFES Process Parameters



Data collection from 30+ NFES papers

Python Image Analysis

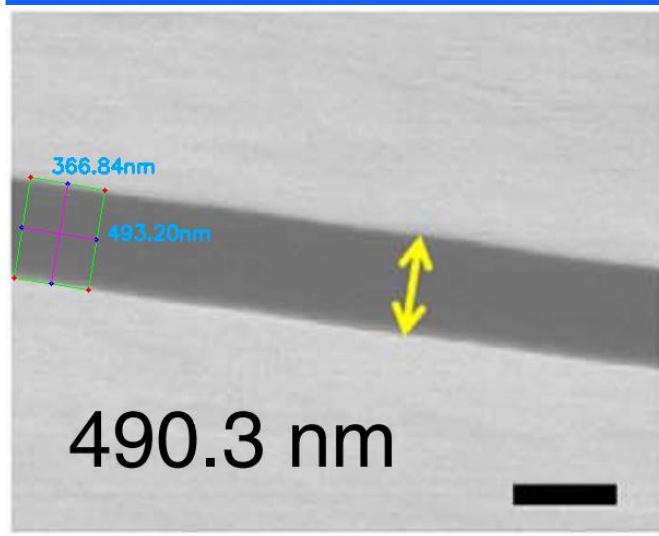


Figure from Min2013

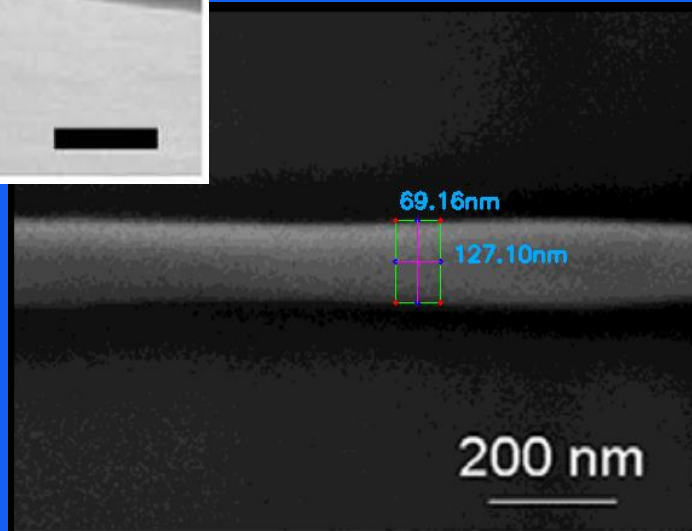
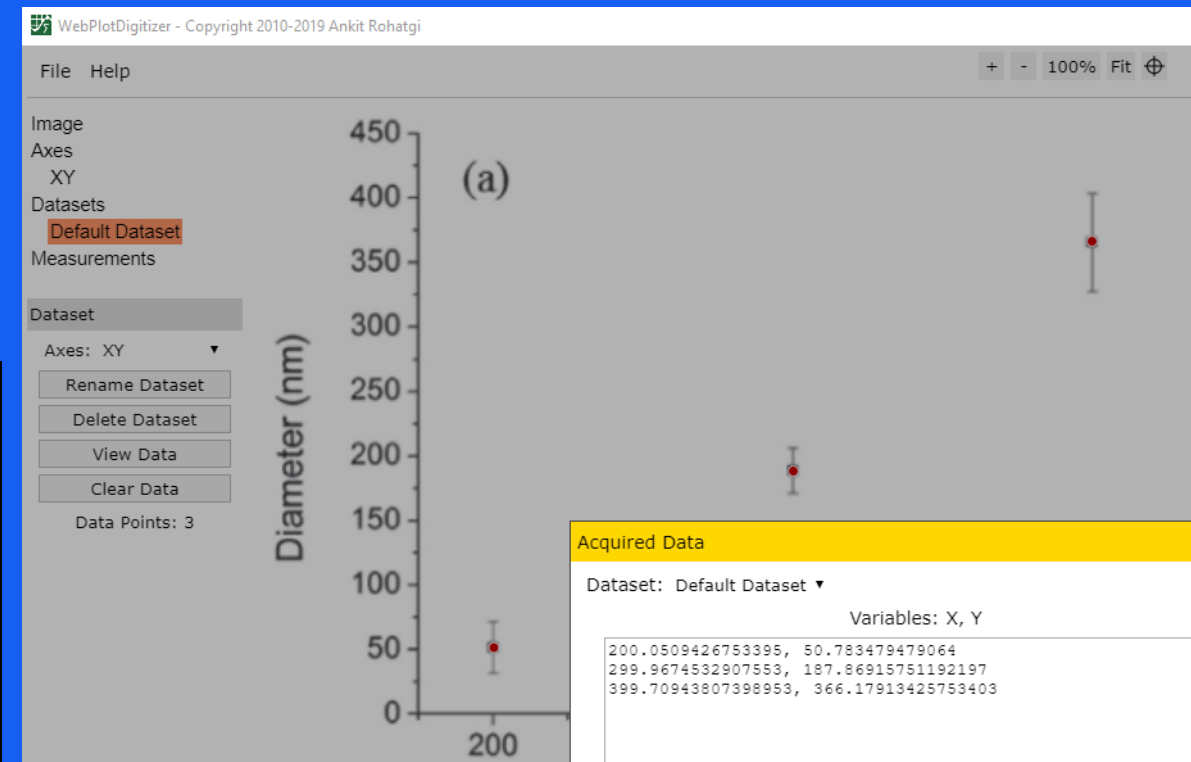


Figure from Camillo2013

WebPlotDigitalizer <https://github.com/ankitrohatgi/WebPlotDigitalizer>



Applied voltage vs. fiber diameter by Madou2011



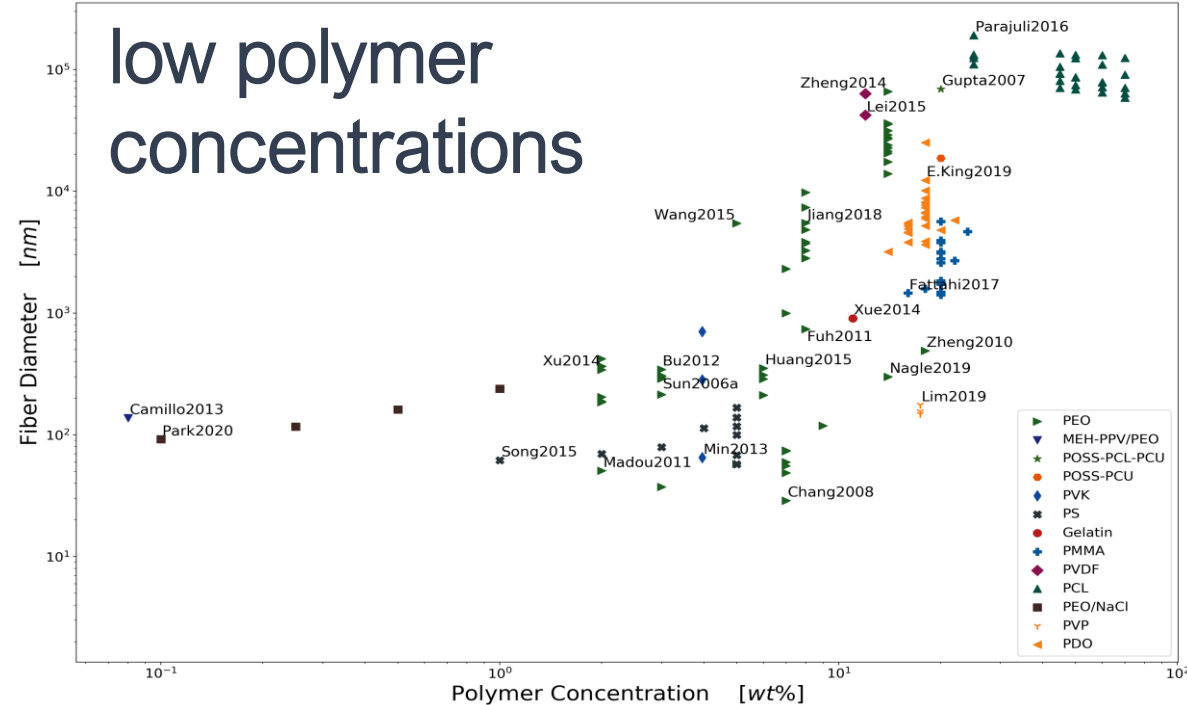
Polymer Concentration,
Nozzle Diameter,
Solution Deposition Rate,
Nozzle to Collector Distance &
Applied Voltage

are the main drivers of the **final
Fiber Diameter**

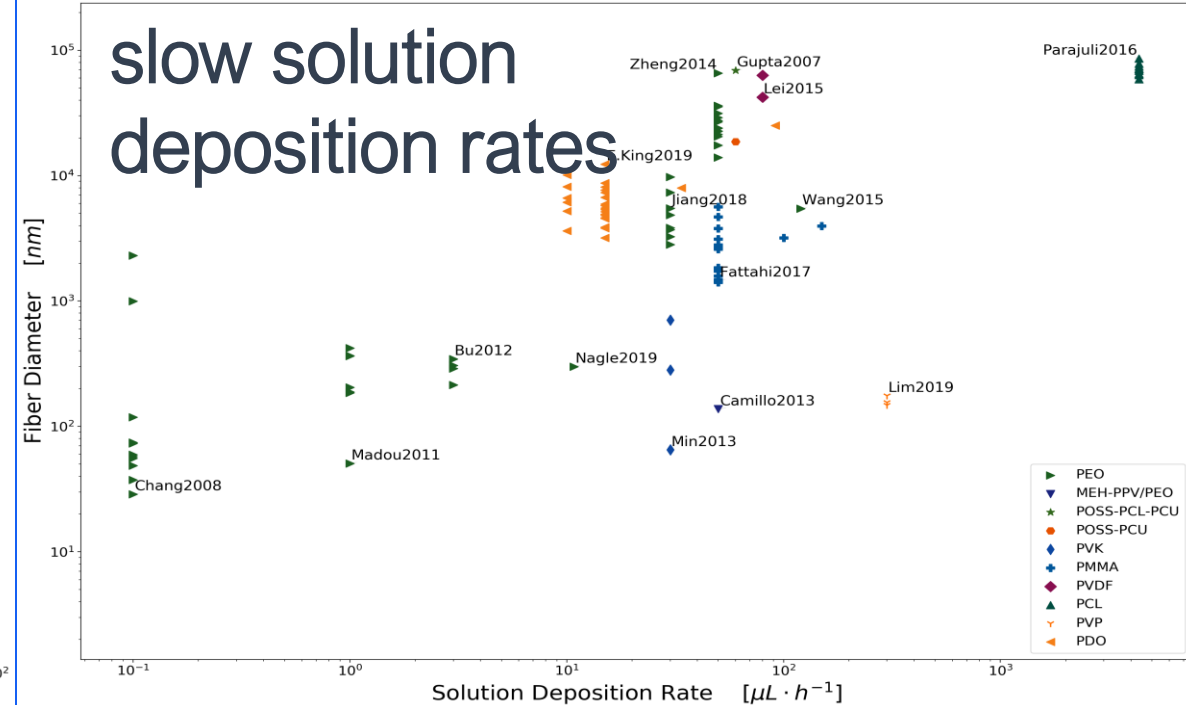
Polymer	1	0	-0	0	-0	-0	-0	0	-0	-0	-0	-0	-0
Polymer Molecular Weight	0	1	0	0	-0	-0	-0	-0	0	-0	-0	-0	-0
Solvent	-0	0	1	0	-1	-0	-0	0	0	-0	0	-0	-0
NFES Type	0	0	0	1	-0	-0	-0	-0	0	-0	-0	-0	-0
Polymer Concentration	-0	-0	-1	-0	1	1	1	0	-0	0	0	1	0
Nozzle Diameter	-0	-0	-0	-0	1	1	0	-0	0	0	0	1	0
Solution Deposition Rate	-0	-0	-0	-0	1	0	1	0	-0	0	0	1	0
Collector Substrate	0	-0	0	-0	0	-0	0	1	0	0	0	0	-0
Nozzle to Collector Distance	-0	0	0	0	-0	0	-0	0	1	0	-0	1	-0
NFES Applied Voltage	-0	-0	-0	-0	0	0	0	0	0	1	0	1	-0
NFES Stage Velocity	-0	-0	0	-0	0	0	0	0	-0	0	1	0	-0
Fiber Diameter	-0	-0	-0	-0	1	1	1	0	1	1	0	1	-0
Distance Between Fibers	-0	-0	-0	-0	0	0	0	-0	-0	-0	-0	-0	1
	Polymer	Polymer Molecular Weight	Solvent	NFES Type	Polymer Concentration	Nozzle Diameter	Solution Deposition Rate	Collector Substrate	Nozzle to Collector Distance	NFES Applied Voltage	NFES Stage Velocity	Fiber Diameter	Distance Between Fibers



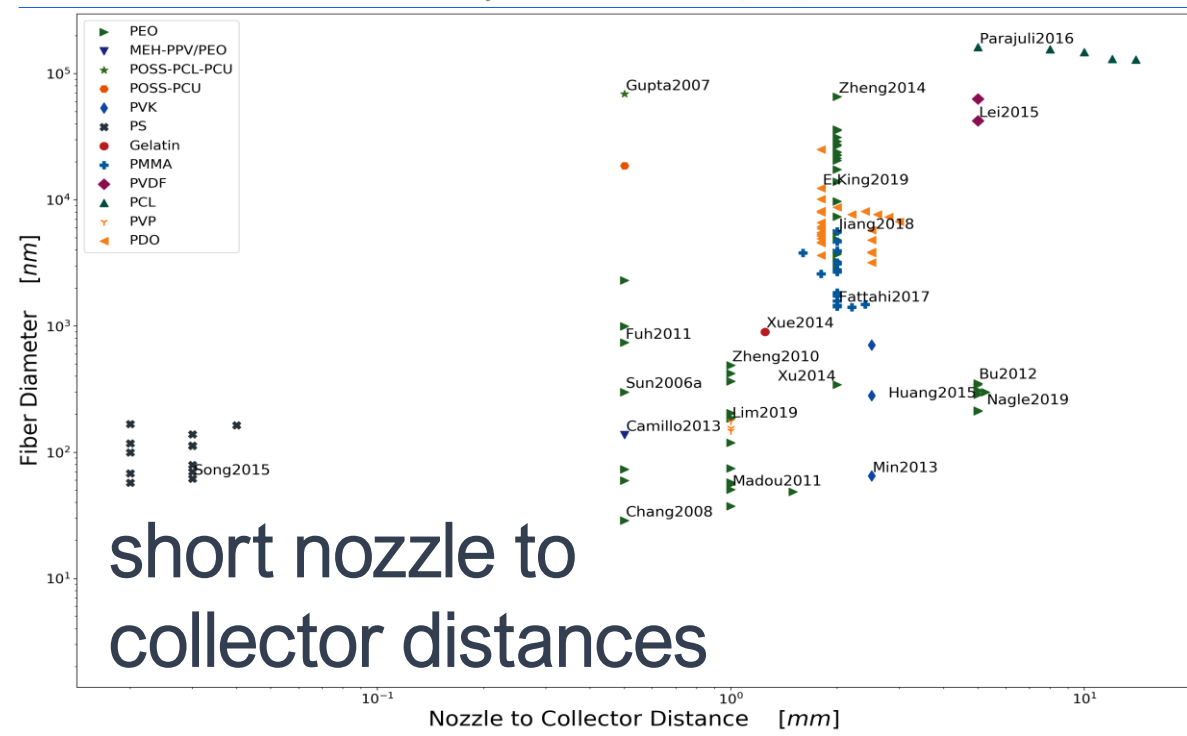
low polymer concentrations



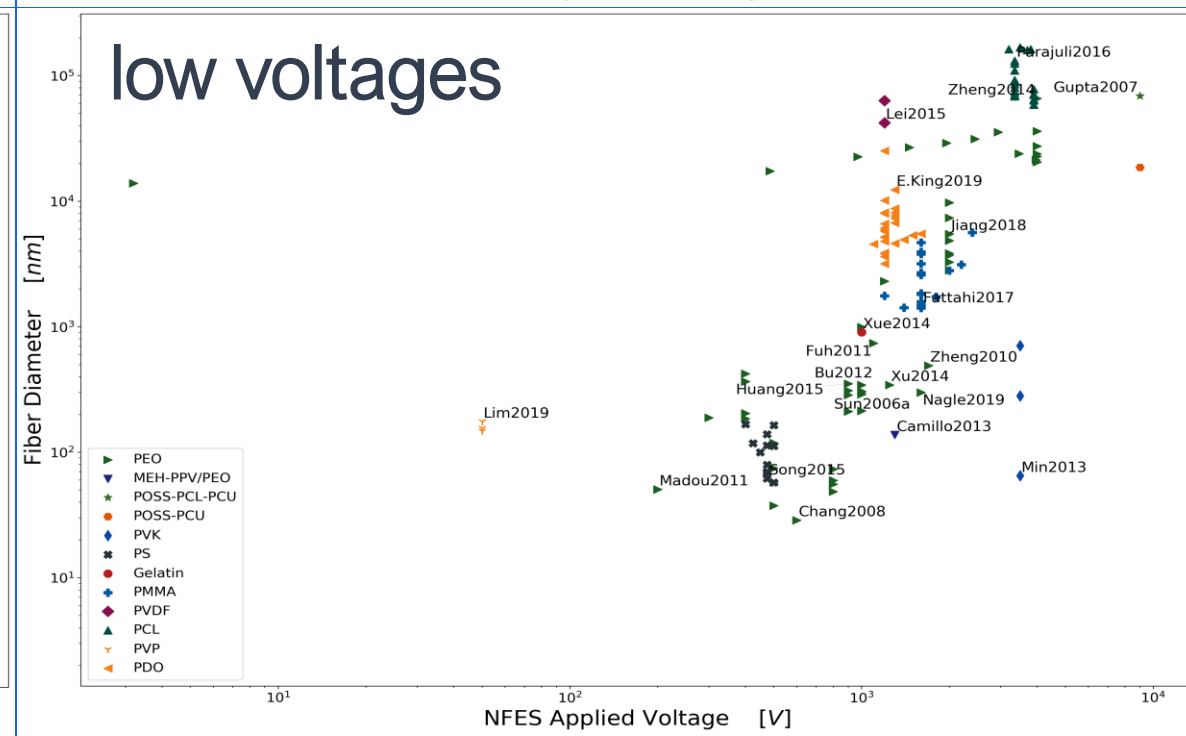
slow solution deposition rates



short nozzle to collector distances



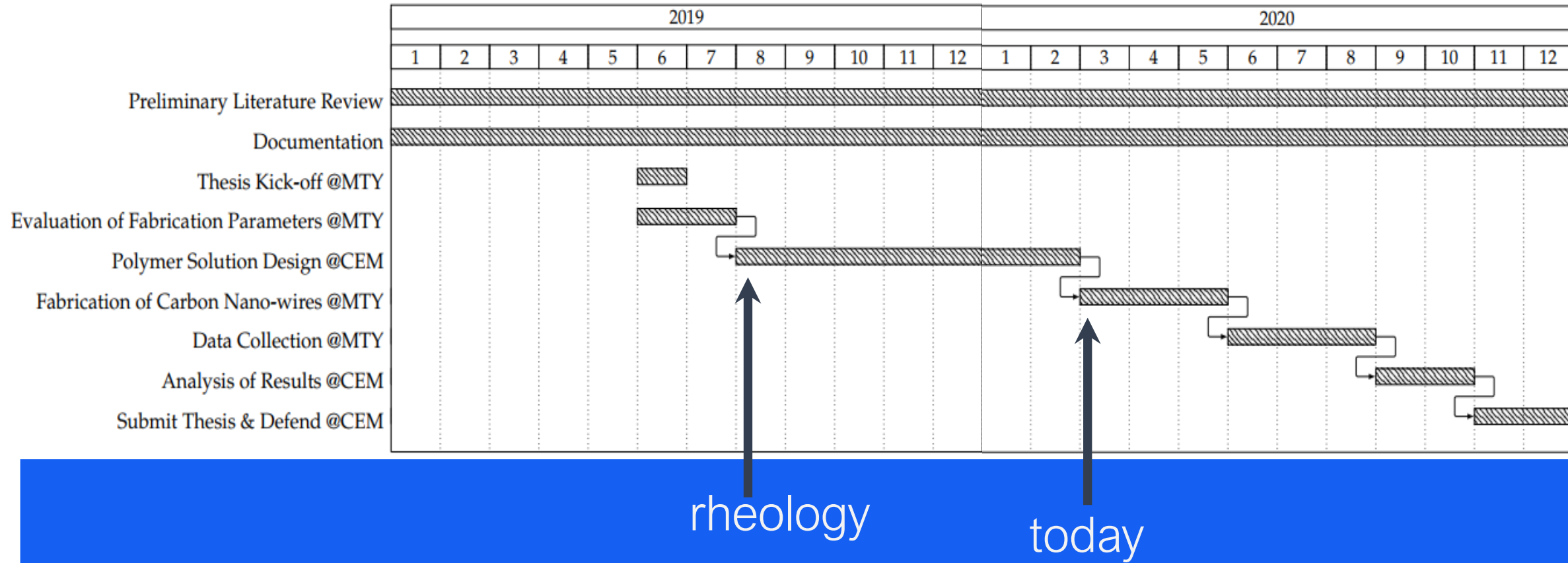
low voltages



Overall Progress & Next Steps



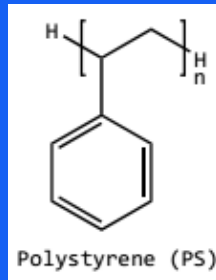
Current Work Plan



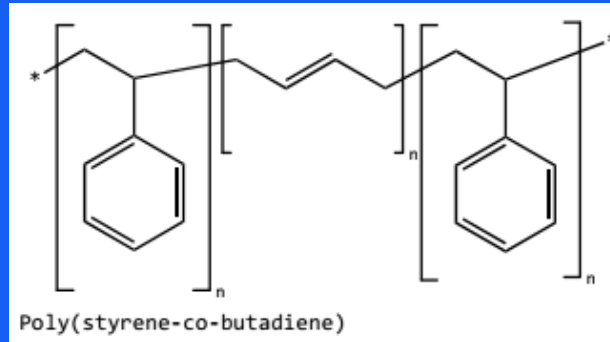
Next step: Study/Test the proposed polymer solutions

high carbon polymers and no oxygen

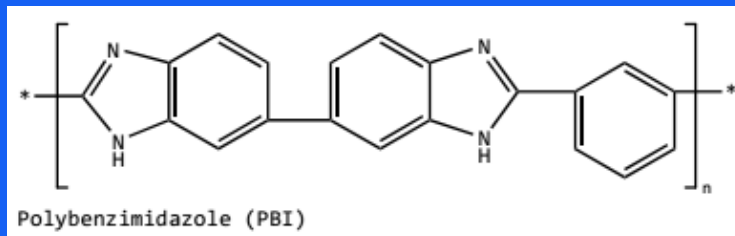
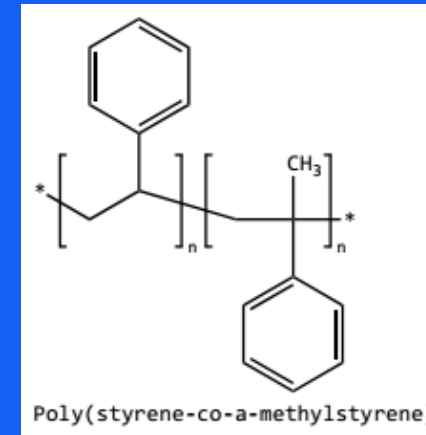
+35 wt% in THF



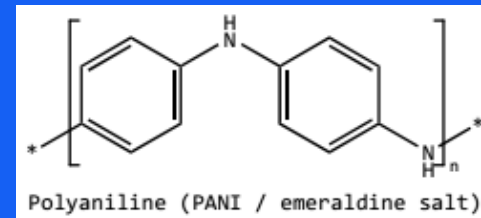
~15 wt% in NMP
~25 wt% in THF & DMF



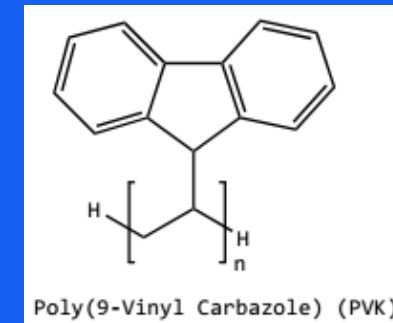
+15 wt% in DMF



No records



No records



~8 wt% in CHL



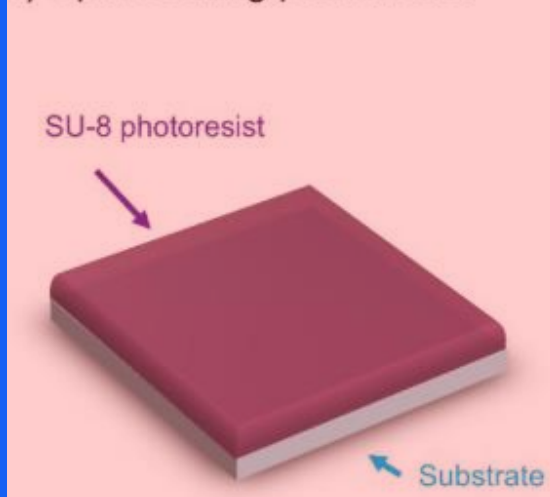


Carbon nanostructures via Lithography

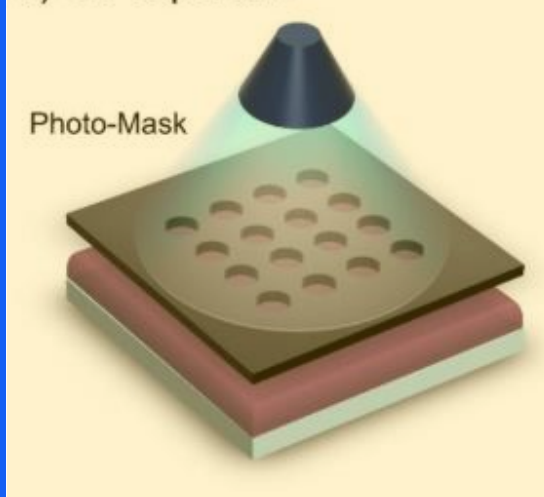
The production of C-MEMS:

1. Polymer patterning through ~~photolithography~~ electrospinning
2. Carbonization through **pyrolysis**

I) Spin-coating photoresist



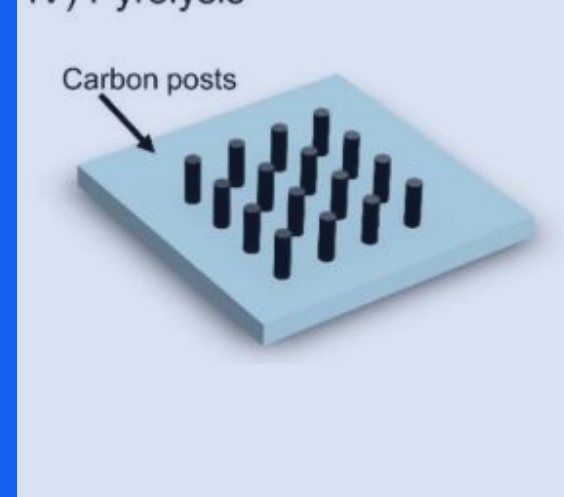
II) UV-exposure



III) Developing



IV) Pyrolysis

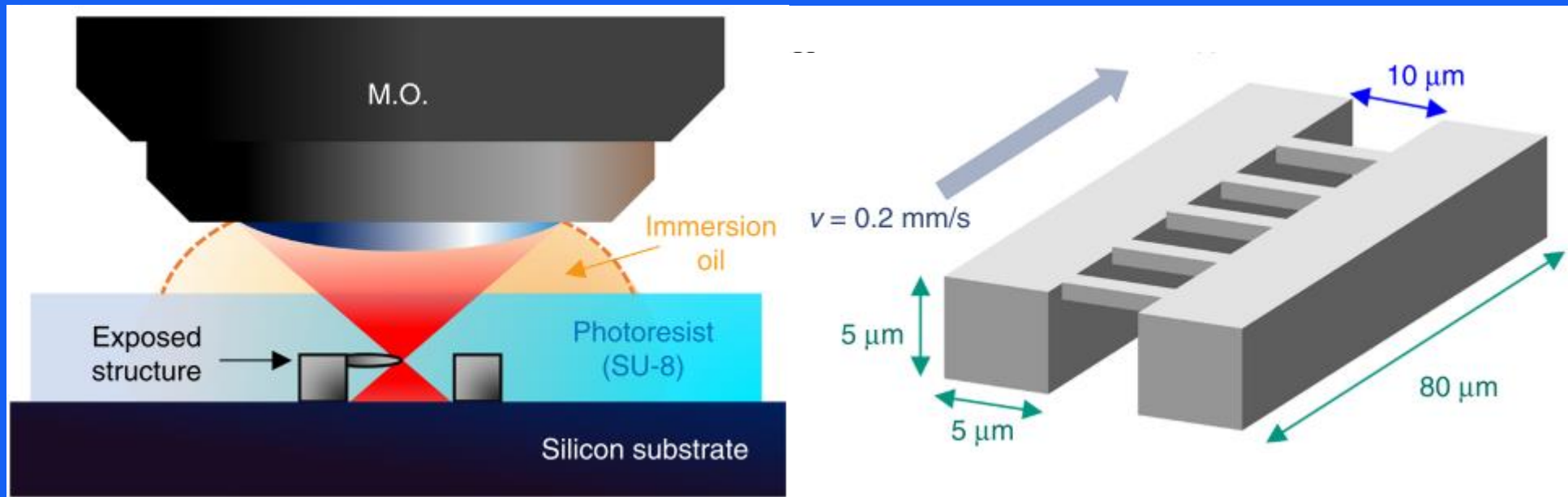


photolithography process

- SU-8 Waste
- Physical & Optical Limitations
- Structure Limitations



TPP – Two-Photon Polymerization

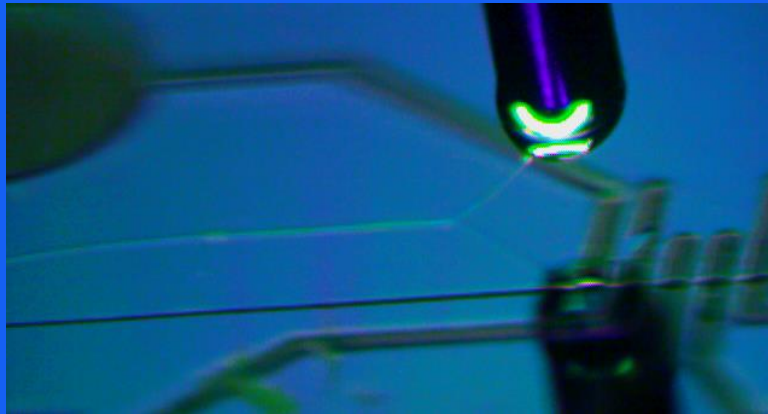


Characterization of the 0.25 wt% PEO Solution



Characterization of the 0.25 wt% PEO Solution

Electrospun-able with an applied voltage of 600V.

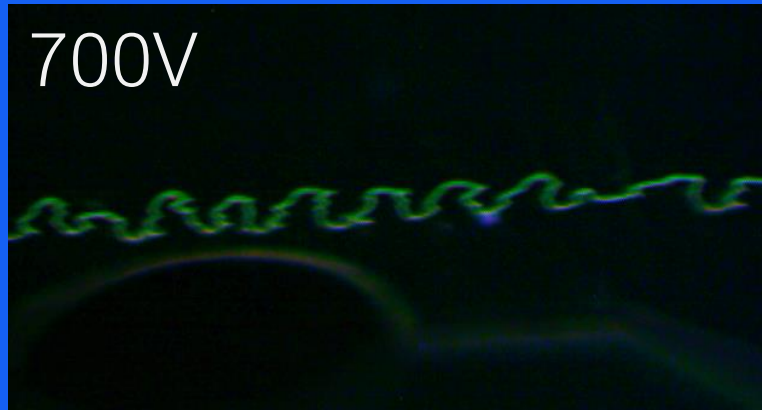


600V



Unable to initiate the jet at 500V or lower.

700V



INF-WIDR_DEP

2 step(s)

Force Level 100%

Syringe

Custom, 1000 ul, 4.78 mm

Step: 1 Constant Rate

Rate: 100 ul/min

Target: 0.5 ul

Step: 2 Constant Rate

Rate: 100 ul/min

Target: 0.4 ul

Time Elapsed: 00:00:01

Total Volume Dispensed: 502.099 nl

Harvard Apparatus

Method complete, ready to start method.



HVS448 3000 V High Voltage Sequencer

ENABLE DISABLE



A

B

C

D

E

F

G

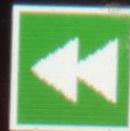
H

ALL

TRIGGER PAUSE



RUN STOP

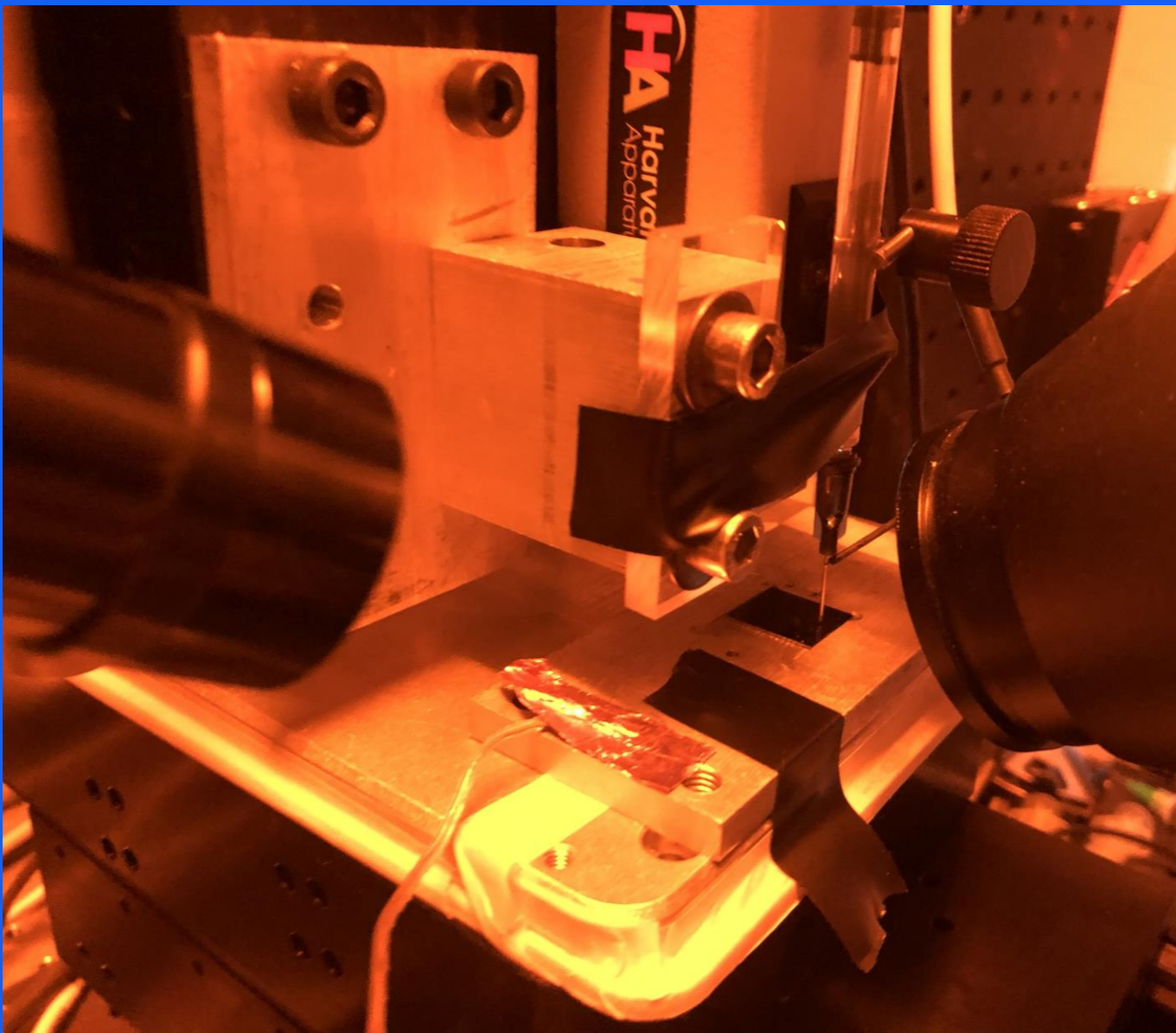


HA Harvard Apparatus



Pump 11 Elite





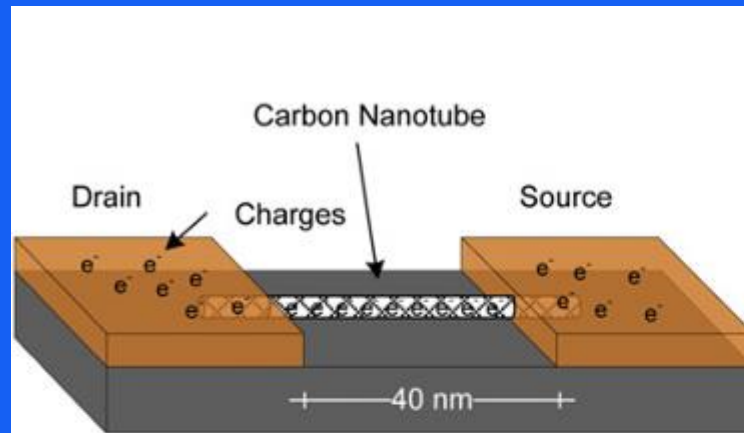
PEO Solution

The EMS polymer solution consisted of 2ml of **SU-8 2002** mixed with 0.5 wt% of **Poly(ethylene oxide)** (PEO, 4,000,000 MW; SigmaAldrich Inc., Cat. N. 189464) and 0.5 wt% **Tetrabutylammonium Tetrafluoroborate** salts (TBATFB; SigmaAldrich Inc., Cat. N. 217964) to increase its conductivity and allow smooth polymer flow during electrospinning.

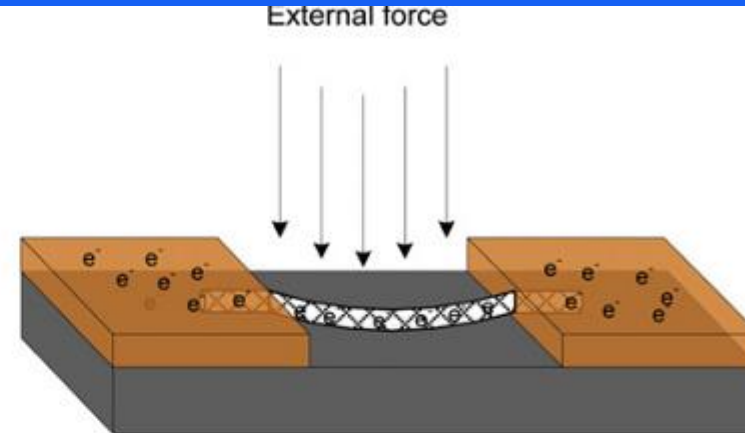
All reagents were used as received. Magnetic stirring of these components was performed for 1hr at 75°C and low rpm (100-150 rpm).



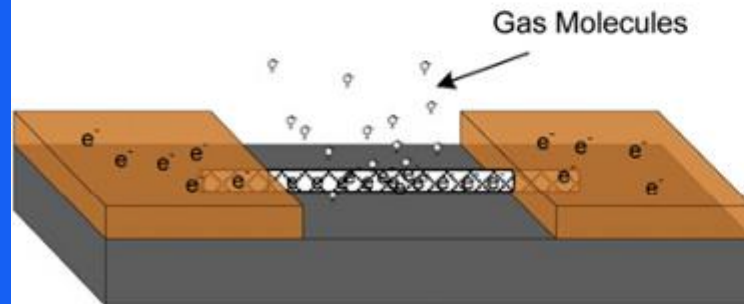
Applications of CNWs



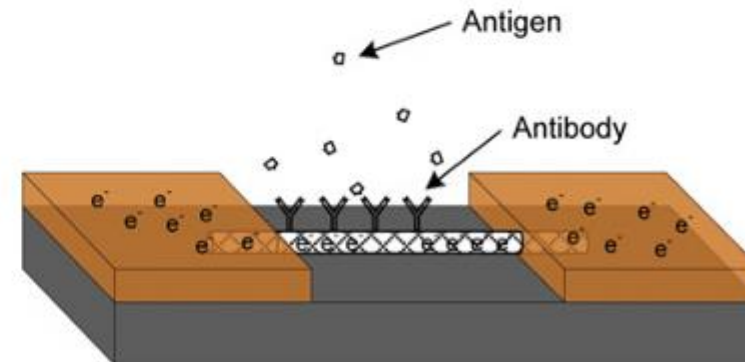
CNT-based FET transistor.



Physical nanosensor.



Chemical nanosensor.

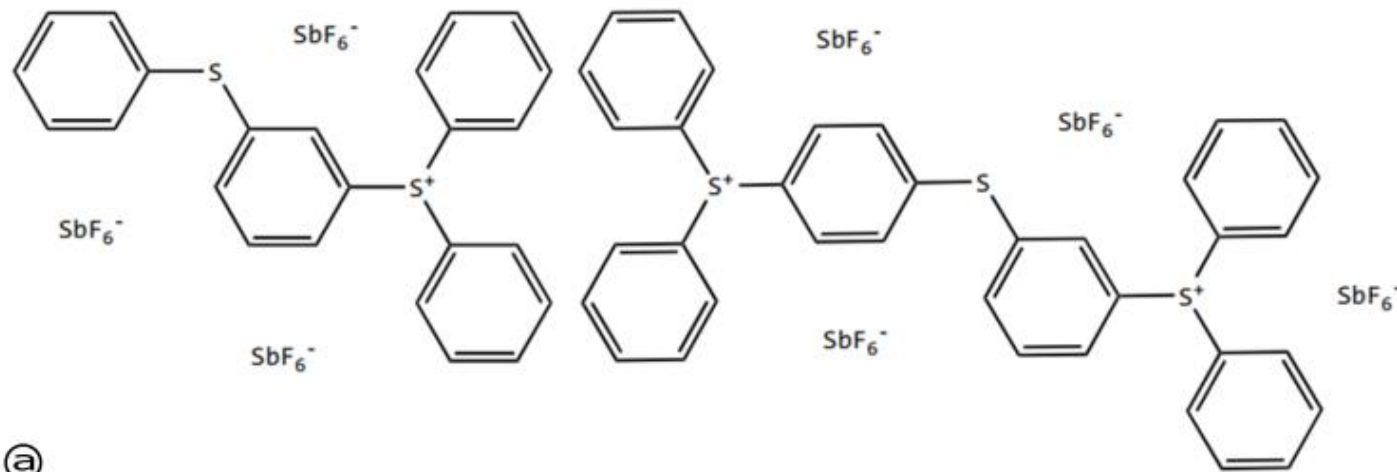
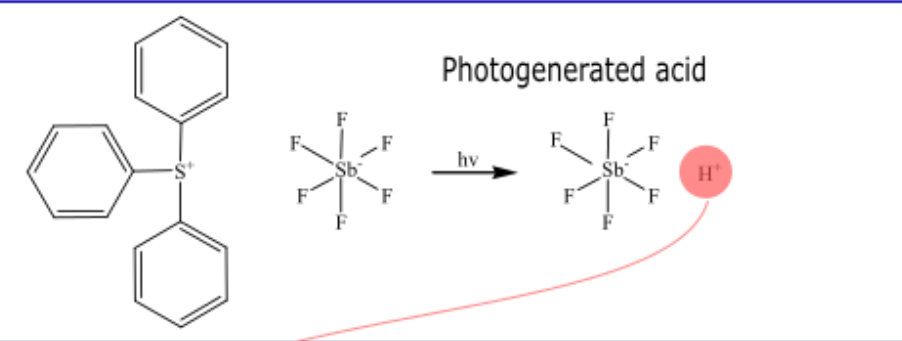


Biological nanosensor.

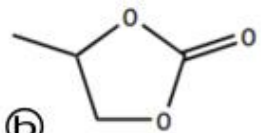


SU-8 (MicroChem,US)

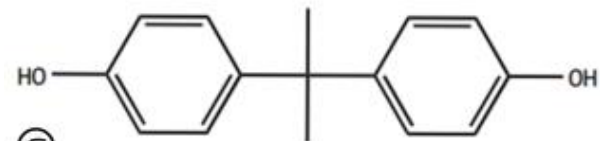
UV irradiation
SU-8 resin



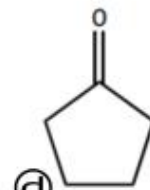
① Mixed Triarylsulfonium/Hexafluoroantimonate Salt (CAS: 89452-37-9)/(CAS: 71449-78-0)



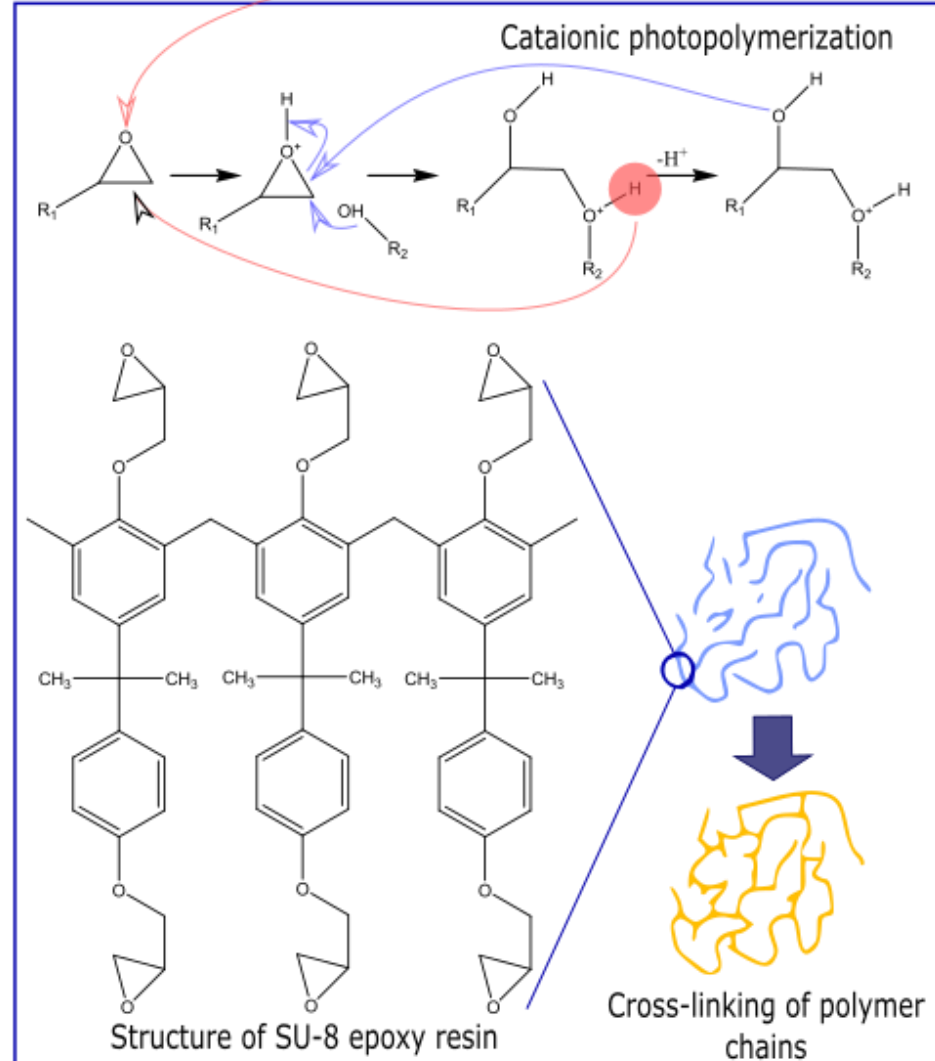
② Propylene Carbonate (CAS: 108-32-7)



③ Epoxy Resin (CAS: 28906-96-9)
2-(Chloromethyl)oxirane; formaldehyde; 4-[2-(4-hydroxyphenyl)propan-2-yl]phenol



④ Cyclopentanone (CAS: 120-92-3)



SU-8 (MicroChem, US)

MICROCHEM CORP SU-8 2002 500ML
encorepass

Manufacturer: MICROCHEM CORP Y111029

Catalog No.	NC0702370
\$628.71 / Each	
Qty	<input type="text"/> Check Availability
Add to cart	

<https://www.fishersci.com/shop/products/NC0702370/nc0702370#?keyword=MICROCHEM+CORP+PHOTORESIST+SU-8>

MICROCHEM CORP SU-8 DEVELOPER 4L
encorepass

Catalog No.	NC9901158
\$172.90 / Each	

INGREDIENTS:

- Cyclopentanone (CAS: 120-92-3); 23-78%.
- Mixed Triarylsulfonium/ Hexafluoroantimonate Salt; (CAS: 89452-37-9)/(CAS: 71449-78-0); 1-5%
- Propylene Carbonate (CAS: 108-32-7); 1-5%
- Epoxy Resin (CAS: 28906-96-9); 25-75%

<https://www.fishersci.com/shop/products/NC9901158/nc9901158#?keyword=SU-8++developer>



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